

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	7190	((jet\$4 or nozzle) or (two adj3 (fluid or liquid) or two-fluid or two-liquid) adj3 (nozzle or jet\$4)) with (move or moving or moved or movement or translat\$4 or position \$4) same (center or periphery or edge) same (wafer or semiconductor or substrate or silicon or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:07
L2	9861	((jet\$4 or nozzle) or (two adj3 (fluid or liquid) or two-fluid or two-liquid) adj3 (nozzle or jet\$4)) with (move or moving or moved or movement or translat\$4 or position \$4 or direction or directed or directing or direct or motion or motioning or motioned) same (center or periphery or edge) same (wafer or semiconductor or substrate or silicon or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:11
L3	1678	(brush or brushing or brushing or scrub or scrubber or scrubbing or scrubbed) with (move or moving or moved or movement or translat\$4 or position \$4 or direction or directed or directing or direct or motion or motioning or motioned) same (center or periphery or edge) same (wafer or	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:13

		semiconductor or substrate or silicon or electronic)				
L4	201	I2 same I3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:13
L5	84	("134"/\$ or "15"/\$). ccls. and I4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L6	2388	mori-t\$.in.	US-PGPUB; USPAT	OR	ON	2009/12/04 20:14
L7	39	amai-m\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L8	4546	sekiguchi-k\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L9	543	orii-t\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L10	1179	ohno-h\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L11	30420	mori-t\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14

L12	47279	tanaka-s\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L13	83896	L6 or L7 or L8 or L9 or L10 or L11 or L12	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L14	6	I4 and L13	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:14
L15	16310	((jet\$4 or nozzle) or (two adj3 (fluid or liquid) or two-fluid or two-liquid) near5 (nozzle or jet\$4)) same (move or moving or moved or movement or translat\$4 or position \$4 or direction or directed or directing or direct or motion or motioning or motioned) same (center or periphery or edge or middle or peripher\$5) same (wafer or semiconductor or substrate or silicon or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:21
L16	3691	(brush or brushing or brushing or scrub or scrubber or scrubbing or scrubbed) same (move or moving or moved or movement or translat\$4 or position \$4 or direction or directed or directing or direct or motion or motioning or motioned) same (center or periphery or edge or peripher\$5) same (wafer or semiconductor or	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:22

		substrate or silicon or electronic)				
L17	491	I15 same I16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:22
L18	84	("134"/\$ or "15"/\$). ccls. and I5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:22
L19	180	("134"/\$ or "15"/\$). ccls. and I17	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:23
L20	10791	((jet\$4 or nozzle) or (two adj3 (fluid or liquid) or two-fluid or two-liquid) near5 (nozzle or jet\$4)) with (move or moving or moved or movement or translat\$4 or position \$4 or direction or directed or directing or direct or motion or motioning or motioned) same (center or periphery or edge or middle or peripher\$5) same (wafer or semiconductor or substrate or silicon or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:24
L21	1862	(brush or brushing or brushing or scrub or scrubber or scrubbing or scrubbed) with (move or moving or moved or movement or translat\$4 or position \$4 or direction or directed or directing or direct or motion or motioning or motioned) same (center or periphery or edge or peripher\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:24

		same (wafer or semiconductor or substrate or silicon or electronic)				
L22	229	I20 same I21	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:25
L23	88	("134"/\$ or "15"/\$). ccls. and I22	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 20:25
S1	4	("20020189641" "20030079764" "20030178047" "6286525").PN.	US-PGPUB; USPAT	OR	ON	2009/12/04 13:56
S2	13	amai-m\$.in.	US-PGPUB; USPAT	OR	ON	2009/12/04 13:59
S3	422	sekiguchi-k\$.in.	US-PGPUB; USPAT	OR	ON	2009/12/04 14:18
S4	91	orii-t\$.in.	US-PGPUB; USPAT	OR	ON	2009/12/04 14:18
S5	513	ohno-h\$.in.	US-PGPUB; USPAT	OR	ON	2009/12/04 14:18
S6	4183	tanaka-s\$.in.	US-PGPUB; USPAT	OR	ON	2009/12/04 14:18
S7	2388	mori-t\$.in.	US-PGPUB; USPAT	OR	ON	2009/12/04 14:18
S8	39	amai-m\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:19
S9	4546	sekiguchi-k\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:19
S10	543	orii-t\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:19

S11	1179	ohno-h\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:20
S12	30420	mori-t\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:20
S13	47279	tanaka-s\$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:21
S14	83896	S7 or S8 or S9 or S10 or S11 or S12 or S13	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:21
S15	182695	("134"/\$ or "15"/\$). ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:22
S16	2324	(nozzle) with (move or moving or moved or movement or translat \$4) with (center or periphery or edge) same (wafer or semiconductor or substrate or silicon or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:23
S17	312	(brush or brushing or brushing) with (move or moving or moved or movement or translat \$4) with (center or periphery or edge) same (wafer or semiconductor or substrate or silicon or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:23

S18	62	S16 and S17	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:23
S19	32	S18 and S15	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:23
S20	7190	((jet\$4 or nozzle) or (two adj3 (fluid or liquid) or two-fluid or two-liquid) adj3 (nozzle or jet\$4)) with (move or moving or moved or movement or translat\$4 or position \$4) same (center or periphery or edge) same (wafer or semiconductor or substrate or silicon or electronic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/04 14:42

EAST Search History (Interference)

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